PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Etienne QUESNEL et al.

Application No.: New U.S. Patent Application

Filed: April 5, 2004 Docket No.: 119364

For: PROCESS DESIGNED TO PREVENT DEPOSITION OF CONTAMINATING PARTICLES ON THE SURFACE OF A MICRO-COMPONENT, MICRO-COMPONENT

STORAGE DEVICE AND THIN LAYER DEPOSITION DEVICE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- 2. Relevance of reference No. 4 is discussed in the present specification.
- 3. The references were cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information.
- 4. The present application was filed or entered the U.S. National Stage of the PCT after June 30, 2003. In accordance with the June 11, 2003, Notice waiving the requirements of 37 CFR §1.98(a)(2)(i), copies of any U.S. patents and patent application publications are not attached.

- 5. An English-language Abstract of non-English language reference No. 2 is attached hereto.
- 6. A computer-generated English translation of the following Japanese Patent Publication has been obtained from the website of the Japanese Patent Office ([http://www.jpo.go.jp]), and is attached, but has not been reviewed for accuracy. See Reference 2.

Respectfully submitted,

William P. Berridge Registration No. 30,024

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WPB:JSA/mxm

Date: April 5, 2004

OLIFF & BERRIDGE, PLC P.O. Box 19928 Alexandria, Virginia 22320 Telephone: (703) 836-6400 DEPOSIT ACCOUNT USE
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Form PTO-1449 (REV. 8-83)				ATTY DOCKET NO. 119364			APPLICATION NO. New U.S. Patent Application				
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(Use several sheets if necessary)				APPLICANTS Etienne QUESNEL et al.							
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		U.S. F	PATEN	NT DOCU	MENTS						
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	2	JP A 7-291790 w/ Abst & Trans	11/7/1995		Japan						
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Date: April 5, 2004